## Notice of References Cited Application/Control No. | Applicant(s)/Patent Under | Reexamination | WANG ET AL. | Examiner | Art Unit | Page 1 of 1

## U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	Α	US-2005/0101147	05-2005	Labelle et al.	438/710
*	В	US-6,136,725	10-2000	Loan et al.	438/758
*	С	US-2005/0074983	04-2005	Shinriki et al.	438/785
*	D	US-2004/0152304	08-2004	Sarigiannis et al.	438/680
*	E	US-5,085,727	02-1992	Steger, Robert J.	156/345.47
*	F	US-6,596,599	07-2003	Guo, Jyh-Chyurn	438/305
*	G	US-6,797,576	09-2004	Teng et al.	438/305
*	Н	US-2004/0241920	12-2004	Hsiao et al.	438/158
	1	US-			
	J	US-			
	к	US-			
•	L	US-			
	М	US-			

## FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	0					
	Р			·		
	Q					
	R					
	S					
	Т					

## **NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Wolf; silicon Processing; Vol. 1, pg 58; para.2 1985; isbn 0-9616721-3-7
	<b>v</b>	Intel: Glossary for Intel's High K, Metal Gate Transistor Announcement; 4/2004
	w	
	x	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.